EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	79863	ion\$1 near3 implant\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/10 12:33
S2	124879	ion\$1 near3 implant\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF .	2006/10/10 03:18
S3	5553	S2 and polyimide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/10 03:18
S4	107	S3 and (polyimide near5 implant\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/10 03:27
S5	42	S4 and resin	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/10 03:21
S6	75	S3 and (polyimide near3 implant\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/10 03:28
S7		S6 and photosensitive and resin	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/10 03:29
S8	6765	polyimide near3 resin and photosensitive	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/10 12:34
S9	399	S8 and (ion\$1 near3 implant\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF .	2006/10/10 13:52

EAST Search History

S10	2	S9 and (implant\$3 near6 polyimide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/10 12:38
S11	. 7	S9 and (implant\$3 same polyimide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/10 12:38
S12	31	S9 and (implant\$6 near5 substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/10 14:22
S13	31411	implant\$ near4 (mask or photoresist or resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/10 14:22
S14	288	S13 and (polyimide near4 (mask or photoresist or resist))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/10 14:25
S15	82	S14 and (photosensitive)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/10 14:31
S16	25	S15 and resin	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/10/10 14:31